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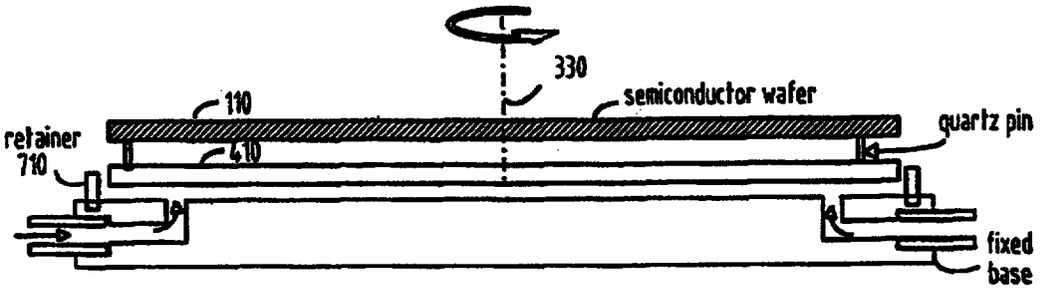
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(54) Title: RAPID THERMAL PROCESSING (RTP) SYSTEM WITH GAS DRIVEN ROTATING SUBSTRATE



(57) Abstract

An apparatus, method, and system for Rapid Thermal Processing (RTP), whereby the object to be processed is rotated under the radiation sources of the RTP system by a gas jet system, are presented.